Amendments to the Claims

- 1. (Currently Amended) An IC fabrication-compatible spiral inductor, comprising
- a) the inductor having <u>vertically</u> stacked planar coils made from a plurality of spaced conductive layers,
- b) the stacked planar coils being electrically connected by coil connectors;
- e) a magnetic core <u>disposed at a center of and extending perpendicular</u> to each of the planar coils and comprising a plurality of vertically stacked and aligned magnetic elements between the plurality of spaced conductive layers and being located within the stacked planar coils.
- 2. (Currently Amended) The inductor of Claim 1, wherein the magnetic element materials are a material forming the magnetic elements is compatible with at least one of CMOS or BiCMOS fabrication technology.
- 3. (Currently Amended) The IC fabrication-compatible spiral inductor of Claim 1, wherein the magnetic elements comprise electrically conductive and magnetic material.
- 4. (Currently Amended) The IC fabrication-compatible spiral inductor of Claim 1, wherein the coil connectors comprise the same material as the magnetic elements.

- 5. (Currently Amended) The IC fabrication-compatible spiral inductor of Claim 4, wherein the magnetic core comprises an array of magnetic element bars within the magnetic core.
- 6. (Withdrawn) The inductor according to Claim 5, further comprising a film of magnetic material located at at least one end of the stacked planar coils.
- 7. (Original) The inductor according to Claim 4, further comprising a film of magnetic material located at at least one end of the stacked planar coils.
- 8. (Currently Amended) The IC fabrication-compatible spiral inductor of Claim 1, wherein the magnetic core comprises an array of magnetic element bars within the magnetic core.
- 9. (Withdrawn) The inductor according to Claim 8, further comprising a film of magnetic material located at at least one end of the stacked planar coils.

- 10. (Original) The inductor according to Claim 1, further comprising a film of magnetic material located at at least one end of the stacked planar coils.
- 11. (Currently Amended) The inductor of Claim 1, wherein the inductor has a footprint dimension of about 75μm x 75μm or less.
- 12. (Currently Amended) The inductor of Claim 1, wherein the inductor is a 10nH inductor with a footprint dimension of less than 25μm x 25μm in a
 0.18μm six layer metal interconnect copper CMOS technology.

Claims 13-27 (Canceled)

- 28. (New) The inductor of Claim 1, wherein each of the magnetic elements is disposed between two of the plurality of spaced conductive layers.
- 29. (New) A single chip IC comprising the inductor of Claim

 1 and a core circuit electrically connected to the inductor.

30. (New) An IC fabrication-compatible spiral inductor, comprising:

a plurality of planar coils disposed in a stacked and parallel orientation; a plurality of coil connectors electrically connecting the planar coils; and

a magnetic core extending perpendicular to and through a center of each of the planar coils.

- 31. (New) The inductor of Claim 30, wherein the magnetic core comprises a plurality of stacked and aligned magnetic elements.
- 32. (New) The inductor of Claim 31, wherein each of the magnetic elements is disposed between two of the plurality of planar coils.
- 33. (New) The inductor of Claim 31, wherein the magnetic elements comprise an electrically conductive and magnetic material.
- 34. (New) The inductor of Claim 31, wherein the magnetic elements and the coil connectors comprise the same material.
- 35. (New) The inductor of Claim 31, wherein the magnetic element materials are compatible with at least one of CMOS or BiCMOS fabrication technology.

- 36. (New) The inductor of Claim 30, wherein the magnetic core comprises an array of parallel magnetic element bars within the magnetic core.
- 37. (New) The inductor of Claim 36, wherein each magnetic element bars of the array of parallel magnetic element bars within the magnetic core comprises a plurality of stacked and aligned magnetic elements.
- 38. (New) The inductor of Claim 36, further comprising a film of magnetic material located at at least one end of the stacked planar coils.
- 39. (New) The inductor of Claim 30, further comprising a film of magnetic material located at at least one end of the stacked planar coils.
- 40. (New) The inductor of Claim 30, wherein the inductor has a footprint dimension of about 75μm x 75μm or less.
- 41. (New) The inductor of Claim 30, wherein the inductor is a 10nH inductor with a footprint dimension of 25μm x 25μm in a 0.18μm six layer metal interconnect copper CMOS technology.

42. (New) A single chip IC comprising the inductor of Claim

29 and a core circuit electrically connected to the inductor.